

Supplementary information

Two-dimensional materials saturable absorbers: Towards compact visible-wavelength all-fiber pulsed lasers

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Chemicals and apparatus. MoS₂ (Product Number 41827), WS₂ (Product Number 11829) and MoSe₂ (Product Number 13112) powders were purchased from Alfa Aesar. NMP, dimethyl formamide (DMF) and lysine were purchased from Green Bird Science and Technology Development (Xiamen, China). All other reagents were of analytical reagent grade, and used as received. Doubly distilled water was used in all the processes of aqueous solution preparation and washing.

Characterization. The micrographs of samples were taken using a TEM (JEOL JEM-2100) with the accelerating voltage of 200 kV. The samples were prepared by placing 20 μL of the colloidal solutions on copper grids coating with lacey carbon film for TEM and were allowed to dry in air. AFM images were acquired in tapping mode in air using a Digital Instrument Nanoscope®. The samples were prepared by placing 20 μL of 10-fold diluted solutions onto the freshly cleaved mica for 5 min, gently rinsed

with deionized water, and dried in vacuum overnight. XRD (Philips PANalytical X'Pert) equipped with Cu K α radiation ($\lambda = 1.542 \text{ \AA}$) over the 2θ range of $10\text{--}80^\circ$ was used to characterize the structure of TMDs. Sample was prepared by depositing a film on the surface of glass slide. The ultraviolet-visible (UV-vis) absorption spectra were measured on UV-vis spectrometer (TU-1901), equipped with 1 cm quartz cells. The spectra were recorded in the wavelength range of 200–800 nm, at a scan speed of 400 nm min⁻¹. Raman spectra (XploRA, Jobin-Yvon) were recorded with a solid-state laser at the excitation wavelength of 532 nm.

Preparation of few-layer MoS₂: The purchased MoS₂ (200 mg) was added into DMF (200 mL) and sonicated for 20 h (KQ-250 DB) to produce the few-layer MoS₂ suspension. Few-layer MoS₂ suspension was centrifuged for 30 min at 2000 rpm to remove bulk MoS₂. Subsequently, the supernatant was decanted to another centrifuge tube. After centrifuging the supernatant at 13000 rpm for 30 min, the as-obtained product was collected into vials and dispersed in the polyvinyl alcohol (PVA) for further application.

Purchased bulk MoS₂ was characterized by XRD (Fig. S1c). All the labeled peaks can be readily indexed to rhombohedral MoS₂ (JCPDS no. 06-0097). The TEM image (Fig. S1a) of exfoliated MoS₂ showed that the as-obtained few-layer MoS₂ was extremely thin 2D flake. Furthermore, the distances between the adjacent hexagonal lattice fringes investigated by HRTEM were 0.205 nm and 0.62 nm for MoS₂ (Fig. S1b), which was consistent with the lattice spaces of the (110) plane and (002) plane. The XRD pattern (Fig. S1c) of few-layer MoS₂ showed a high [002] orientation and some characteristic peaks disappeared compared to bulk MoS₂, which indicated that bulk MoS₂ had been successfully exfoliated. As shown in Fig. S1d, Raman spectroscopy, a powerful nondestructive characterization tool, was also used to estimate the thickness of few-layer MoS₂. The two characteristic peaks at 380 and 410 cm⁻¹ are assigned to E_{2g}¹ and A_{1g} modes of the bulk MoS₂. Compared with the bulk MoS₂, few-layer MoS₂ sample shows an obvious red shift of E_{2g}¹ peak and blue shift of A_{1g} peak, indicating that the MoS₂ was successfully exfoliated with a thickness of

1-4 layers [s1]. Furthermore, the thickness of the as-prepared few-layer MoS₂ was characterized by AFM, as shown in Fig. S1e. The average thickness from the height profile (Fig.S1e insert) was measured to be ~2-3 nm. This result indicates that the MoS₂ nanosheets are around 3-4 layers, because the thickness of single-layer MoS₂ is 0.65 nm [s2]. Fig. S1f shows the absorption spectra of the few-layer MoS₂ dispersion, which is close to that expected [s3].

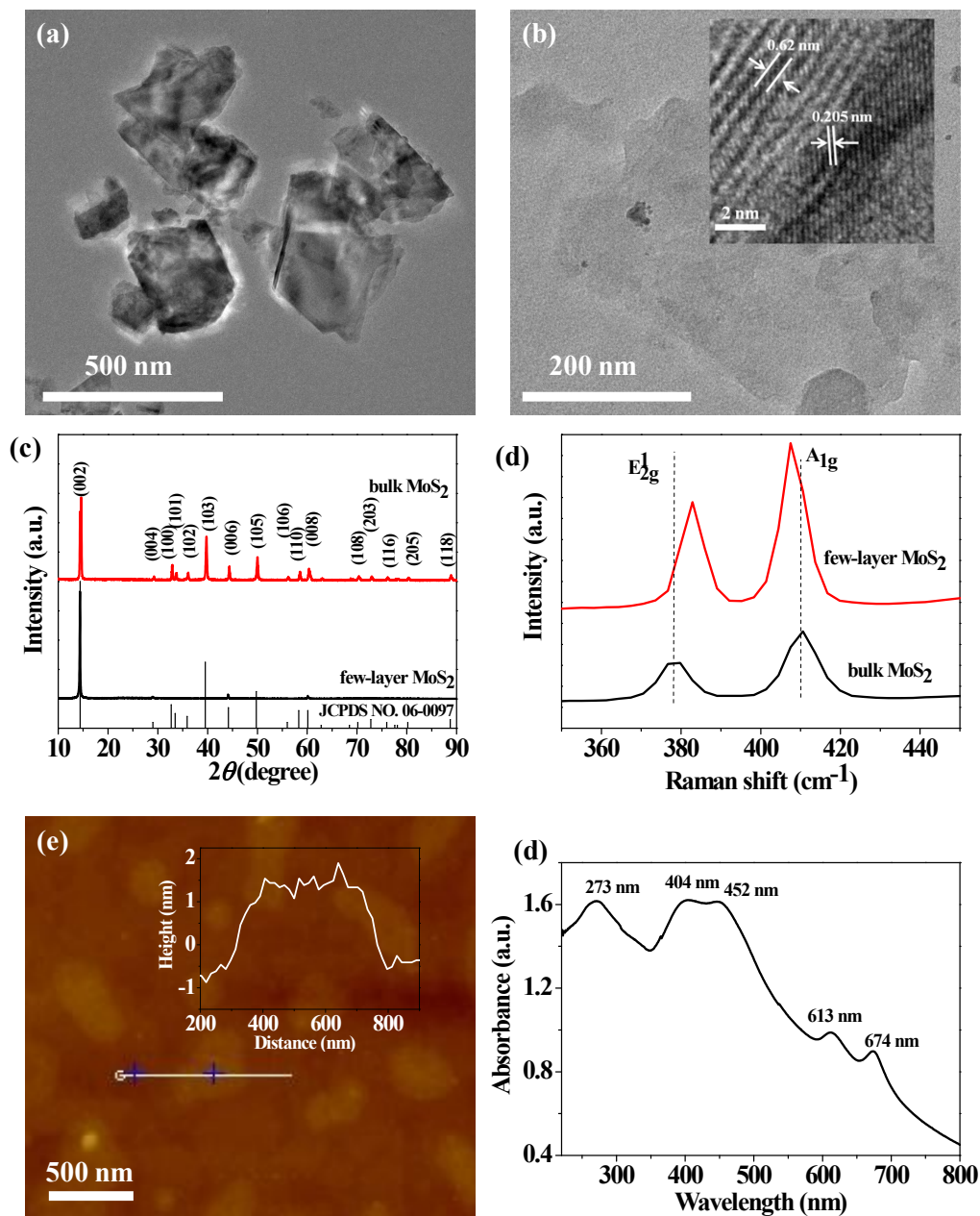


Fig. S1. (a) TEM image of few-layer MoS₂. (b) HRTEM image of few-layer MoS₂. (c) XRD patterns of bulk MoS₂ and few-layer MoS₂. (d) Raman spectra of bulk MoS₂ and few-layer MoS₂. (e) AFM image of few-layer MoS₂. Insert: corresponding height profile of few-layer MoS₂. (f) UV-vis absorption spectrum of the few-layer MoS₂.

Preparation of few-layer MoSe₂: The purchased MoSe₂ (200 mg) was added into the 1 mg mL⁻¹ lysine solution (200 mL) and sonicated for 20 h (KQ-250 DB) to produce the few-layer MoSe₂ suspension. Few-layer MoSe₂ suspension was centrifuged for 30 min at 1000 rpm to remove bulk MoSe₂. Subsequently, the supernatant was decanted to another centrifuge tube. After centrifuging the supernatant at 13000 rpm for 30 min to remove free lysine, the as-obtained product was collected into phials and dispersed in the polyvinyl alcohol (PVA) for further application.

Bulk MoSe₂ was characterized by XRD (Fig. S2c). All the labeled peaks can be readily indexed to rhombohedral MoSe₂ (JCPDS no. 29-0914). The TEM image (Fig. S2a) of exfoliated MoSe₂ showed that the as-obtained few-layer MoSe₂ was extremely thin 2D flake. Furthermore, the distance between the adjacent hexagonal lattice fringes investigated by HRTEM was 0.28 nm for MoSe₂ (Fig. S2b), which was consistent with the lattice space of the (10-10) plane. The XRD pattern (Fig. S2c) of few-layer MoS₂ showed the existence of high [002] orientation and some characteristic peaks disappeared compared to bulk MoSe₂, which indicated that bulk MoSe₂ had been successfully exfoliated. As shown in Fig. S2d, the A_g¹ Raman mode of the few-layer MoSe₂ was red-shifted slightly, also confirming that the few-layer structure of the as-prepared MoSe₂ [s4]. Furthermore, the thickness of the as-prepared few-layer MoSe₂ was characterized by AFM (Fig. S2e). The average thickness from the height profile (Fig. S2e insert) was measured to be ~2-4 nm. This result indicates that the few-layer MoSe₂ is around 3-6 layers, because the thickness of single-layer MoSe₂ is about 0.65 nm [s5]. Fig. S2f shows the absorption spectrum of the few-layer MoSe₂ dispersion, which is close to that expected [s3].

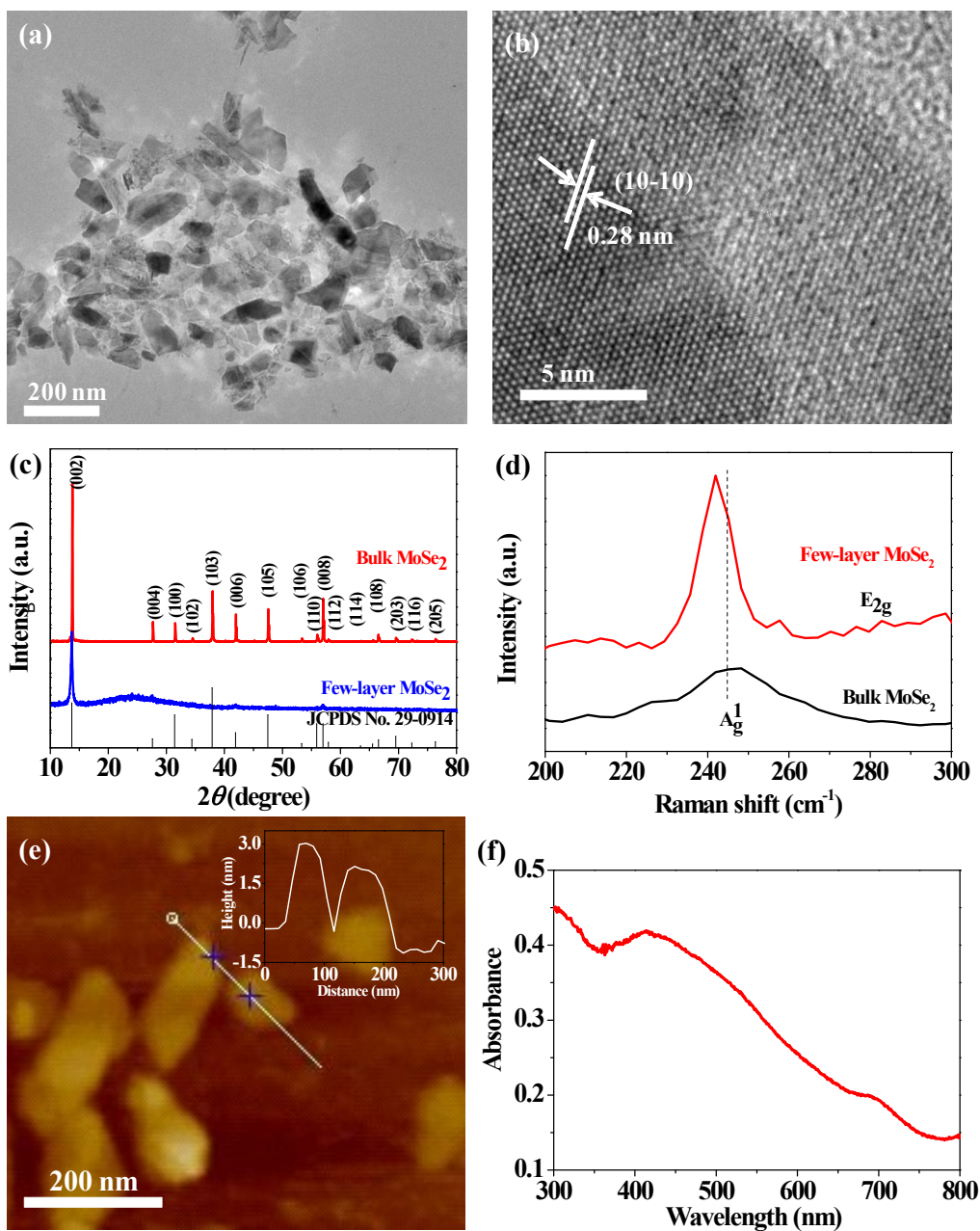


Fig. S2. (a) TEM image of few-layer MoSe₂. (b) HRTEM image of few-layer MoSe₂. (c) XRD patterns of bulk MoSe₂ and few-layer MoSe₂. (d) Raman spectra of bulk MoSe₂ and few-layer MoSe₂. (e) AFM image of few-layer MoSe₂. Insert: corresponding height profile of the few-layer MoSe₂. (f) UV-vis spectrum absorption of the few-layer MoSe₂.

OA Z-scan measurement of the few-layer WS₂ at 530 nm: We have experimentally performed the Z-scan measurement of the few-layer WS₂ at a green wavelength of 530 nm. As can be seen in Fig.S3, the few-layer WS₂ also shows the strong saturable absorption at 530 nm. The modulation depth can be as high as ~13%. Therefore, we believe that such 2D TMDs-based SAs could be available for green-wavelength passively Q-switched or mode-locked laser too. In addition, because the few-layer WS₂ sample has the strong linear absorption in the blue-wavelength region, we did not perform the corresponding Z-scan measurement at blue wavelength.

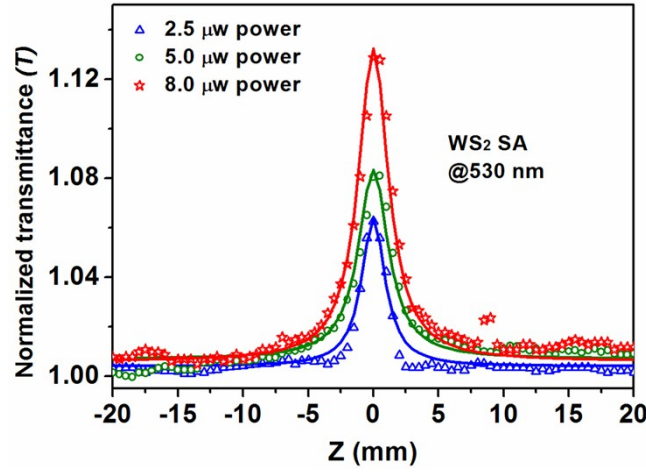


Fig. S3. OA Z-scan traces with the excitation wavelength of 530 nm and the excitation powers of 2.5, 5.0 and 8.0 μ W, respectively.

Emission spectrum of the Pr³⁺-doped ZBLAN fiber: As shown in Fig. S4, we measured the emission spectrum of the used Pr³⁺-doped fiber excited by a 445 nm laser diode. In the reflective waveband (580~710 nm) of the cavity mirror M1 used in our experiment, there are a few of emission peaks at 609.3, 635.2 and 716.5 nm, respectively. However, it should be noted that the 635.2 nm emission peak with a spectral bandwidth of ~7 nm is highest, indicating that the optical gain of the Pr³⁺-doped fiber around 635.2 nm is strongest. Although other emission peaks of 609.3 and 716.5 nm are also covered by the cavity mirror M1, the gain competition in the Pr³⁺-doped fiber finally leads to the ~635 nm lasing only.

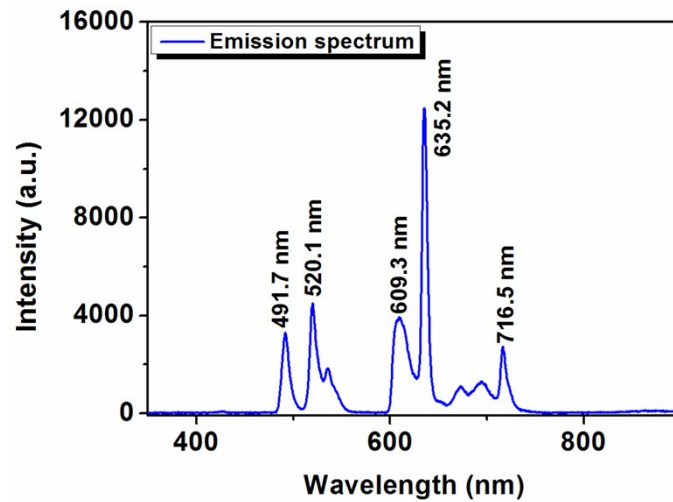


Fig.S4 The emission spectrum of the Pr³⁺-doped ZBLAN fiber excited by a 445 nm LD.

The experimental results of MoS₂ passively Q-switched fiber laser at 635.5 nm.

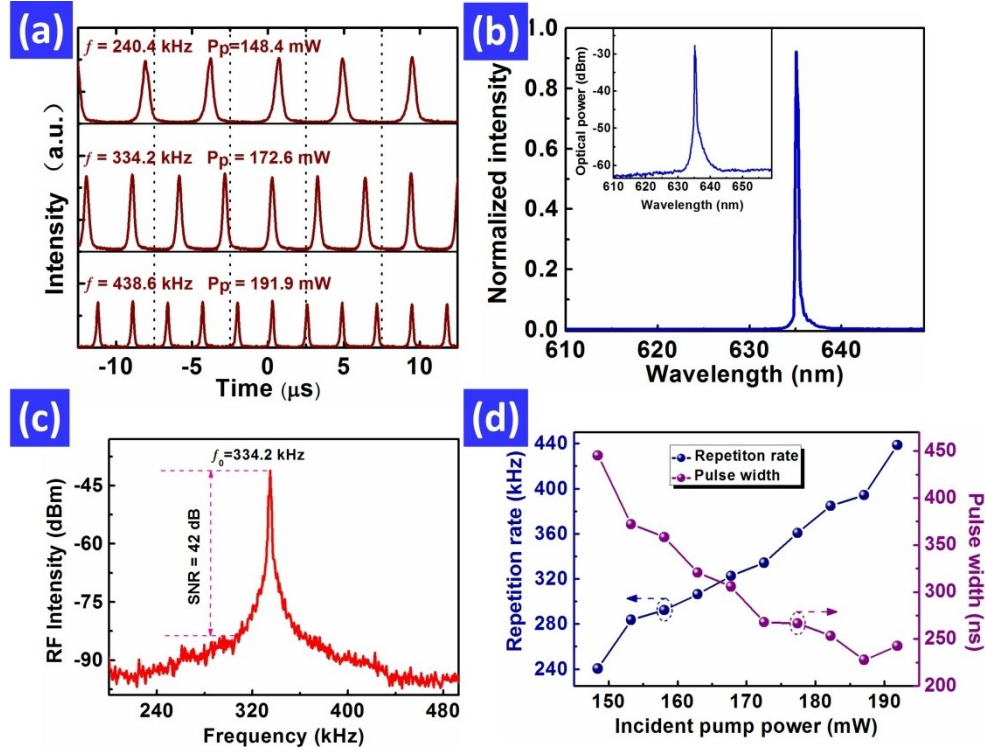


Figure S5 | The output performance of MoS₂ passively Q-switched red fiber laser. (a), The Q-switched pulse trains under the incident pump powers of 148.4 mW, 172.6 mW and 191.9 mW, respectively. (b), Output optical spectrum at the center wavelength of 635.1 nm. (c), RF output spectrum at the fundamental frequency of 334.2 kHz. (d), The pulse repetition rate and the pulse duration as a function of incident pump power.

With MoS₂ SA, continuous-wave (CW) operation occurred at an incident pump power of 121.9 mW, and Q-switched operation started at the incident pump power of 148.4 mW. Figure S5(a) show the typical oscilloscope traces of the Q-switched pulse trains under the pump power of 148.42, 172.6 and 191.9 mW. From Fig. S5(b), the lasing wavelength locates at 635.5 nm. As shown in Fig. S5(c), the signal-to-noise ratio (SNR) of fundamental frequency at 334.2 kHz is ~42 dB, indicating that the Q-switching operation is stable. By varying the pump power from 148.4 to 191.8 mW, the pulse repetition rate can be widely tuned from 240.4 to 438.6 kHz and the pulse duration becomes shorter and shorter with the narrowest of 227 ns, as shown in Fig. S5(d).

The experimental results of MoSe₂ passively Q-switched fiber laser at 635.4 nm.

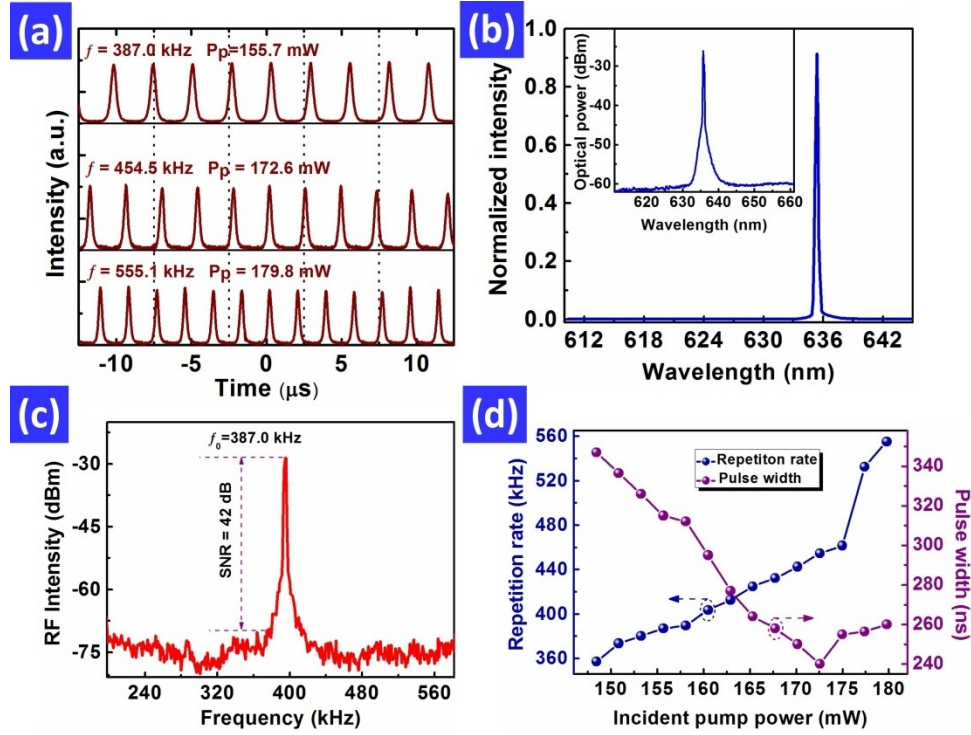


Figure S6 |The output performance of MoSe₂ passively Q-switched red fiber laser. (a), The Q-switched pulse trains under the incident pump powers of 155.7 mW, 172.6 mW and 179.8 mW, respectively. (b), Output optical spectrum at the center wavelength of 635.4 nm. (c), RF output spectrum at the fundamental frequency of 387.0 kHz. (d), The pulse repetition rate and the pulse duration as a function of incident pump power.

The MoSe₂ SA-based Q-switched red fiber laser was also achieved and measured. The CW laser threshold is 105.7 mW and the Q-switched operation occurred at the incident pump power of 146.8 mW. The typical Q-switched pulse trains with repetition rate of 387.0, 454.6 and 555.1 kHz are shown in Fig. S6(a). The center wavelength of the red laser is 635.4 nm from Fig. S6(b). The red Q-switched pulse train is stable, just as shown in Fig. S6(c), the SNR of fundamental frequency at 387.0 kHz is ~42 dB. By changing the incident pump power from 146.8 to 179.8 mW, the pulse repetition rate gradually increases from 357.1 to 555.1 kHz, and the pulse duration almost decreases linearly to the narrowest of 240 ns, as shown in Fig. S6(d).

Plasma sputter deposition system (SCT-S500):

The fiber pigtail mirror with the high-reflectivity at 635 nm was coated by Remote plasma sputtering method. The plasma sputter thin-film deposition system (SCT-S500) from the System Control Technology Inc. was used in our experiment, and the system's structure is shown in Fig. S7. An RF coil antenna surrounding a quartz tube is attached to the vacuum chamber as a side arm. The plasma is initiated and amplified by a DC launch electromagnet towards the plasma source exit. By altering the current applied to the electromagnet and in particular to the steering electromagnet, the position of the plasma beam can be adjusted to ensure good beam impingement on the target surface. To achieve a high deposition rate in reactive process, the RF power was adjusted from 1-2.2 kW and the target negative bias voltage was set from 300V-700 V respectively. During the deposition process, the system was pumped using cryo-pump with a base pressure of 6×10^{-6} Torr. Pure Argon gas was introduced to the chamber by placing a diffusion ring close to the target, and the oxygen was fed into the chamber through another diffusion ring placed as close as possible to the substrate. The oxygen flow was regulated from 0-30 sccm, the argon flow was fixed at 85 sccm, and the background pressure is approximately 5×10^{-3} Torr level. The fiber-pigtails were used to deposit the films. Transmission measurements were performed using Perkin-Elmer Lambda 750 spectrometer.

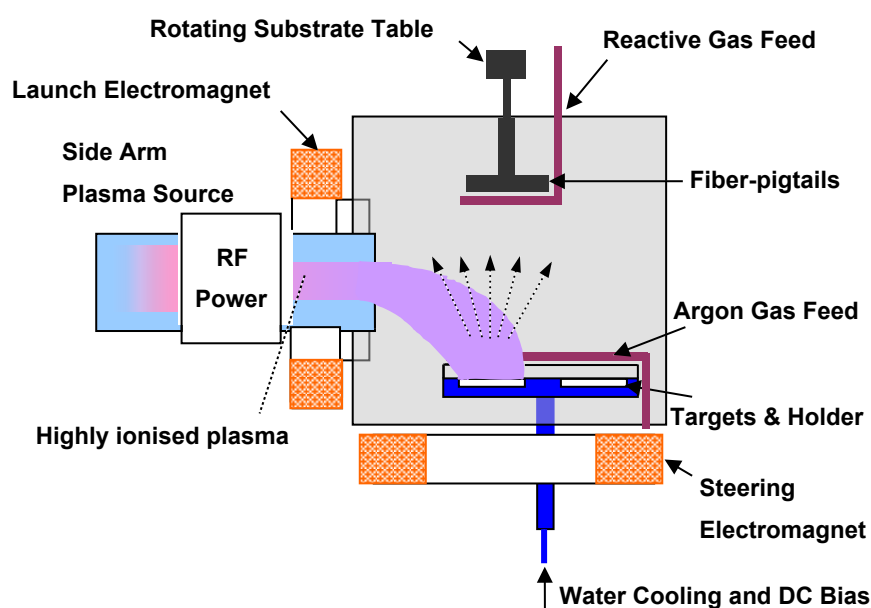


Figure S7 | The remote plasma sputtering deposition schematic drawing.

References

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